THIN-FILM MATERIALS
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Certificate of Analysis (CoA)

Dec. 2, 2025

Product Name: Cobalt Iron Boron Sputtering Target
Chemical Formula: CoFeB (20/60/20 at%)
Purity: 99.95% (3N5)
Dimensions: Ø50.8 mm (2”) × 1.5 mm (±0.05 mm)
Backing Plate: None
Quantity: 2 pcs
Lot Number: CSJM-251202TB
Manufactured by: Thin-Film Materials

Physical Description

- Form: Metallic alloy sputtering target
- Appearance: Metallic gray, smooth machined surface
- Fabrication: Vacuum melted alloy, hot-pressed, and precision machined
- Crystal Structure: Amorphous / nanocrystalline alloy (composition dependent)
- Theoretical Density: ~7.3–7.5 g/cm³

Chemical Composition (by GDMS / ICP-OES)

Element	Symbol	Max. Content (ppm)
Cobalt	Co	Balance
Iron	Fe	Balance
Boron	B	Balance
Nickel	Ni	<30
Chromium	Cr	<30
Silicon	Si	<20
Aluminum	Al	<20
Copper	Cu	<20
Carbon	C	<100
Oxygen	O	<100

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Element	Symbol	Max. Content (ppm)
Other elements (each)	–	<10
Total Impurities	–	<500 ppm

Handling & Storage

- Store in vacuum-sealed packaging.
- Avoid moisture, fingerprints, and corrosive environments.
- Handle with clean gloves to prevent surface contamination.

Declaration

This product has been manufactured and tested according to our quality control standards and meets the specifications stated herein.

Authorized Signature:

Inspection Certificate by: **Nancy Liu**

Approver by: **Chen Qiang** Chen Qiang